WEST Search History

| Hide Items | Restore | Clear | Cancel |

DATE: Monday, January 23, 2006

Interference Search

Hide?	Set Name	Query	Hit Count
		DB=PGPB, USPT; PLUR=YES; OP=OR	
☐	L5	L4 and L3 and L2 and L1	4
☐	L4	base.clm.	579955
☐	L3	developer.clm.	18077
☐	L2	photoresist.clm. or resist.clm.	56234
☐	L1	immersion.clm.	7918

END OF SEARCH HISTORY

WEST Search History

| Hide Items | Restore | Clear | Cancel |

DATE: Monday, January 23, 2006

Hide?	Set Name	Query	Hit Count
		DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=OR	
☐	L19	L17 with L2 with L4	424
☐	L17	expos$4	2144338
☐	L16	L10 same L8	777
☐	L15	L14 same L9	16
☐	L14	L13 same L3	166
☐	L13	L2 adj L12	390
☐	L12	lithography	75295
☐	L11	L10 same L9	1331
☐	L10	L2 same L3	5342
☐	L9	L8 or base	5459306
☐	L8	L7 or L6 or L5	1240493
☐	L7	amine	606262
☐	L6	phosphate	525067
☐	L5	hydroxide	579959
☐	L4	developer	200379
☐	L3	photoresist or resist	684321
☐	L2	immersion	142835

END OF SEARCH HISTORY